IN THE CLAIMS

Claims 1-25 (Canceled).

Claim 26 (New): A vapor deposition material comprising a polycrystalline body, a sintered body, or single crystal having a surface covered with a fluoride layer, wherein the fluoride layer comprises a material of formula

MO_XF_Y

wherein M is Mg, Ca, Sr, Ba, an alkali earth compound metal, a rare earth metal, or a compound metal of an alkali earth metal and rare earth metal, and 0 < X < 2 and $0 \le Y \le 4$.

Claim 27. (New): The vapor deposition material according to claim 26 wherein said polycrystalline body, sintered body, or single crystal is formed from one or more oxides selected from the group consisting of MgO, CaO, SrO, BaO, an alkaline earth composite oxide, a rare earth oxide, and a composite oxide of an alkaline earth oxide and a rare earth oxide.

Claim 28 (New): The vapor deposition material according to claim 26, wherein said fluoride layer is obtained by reacting a fluoridation agent with one or more oxides selected from the group consisting of MgO, CaO, SrO, BaO, an alkaline earth composite oxide, a rare earth oxide, and a composite oxide of an alkaline earth oxide and a rare earth oxide.

Claim 29 (New): An FPD obtained by vapor depositing the vapor deposition material according to claim 26 onto a substrate.

Claim 30 (New): The vapor deposition material according to Claim 26, wherein the fluoride layer is from 0.1 nm to 100 μ m in thickness.

Claim 31 (New): The vapor deposition material according to Claim 26, wherein the fluoride layer is from 1 nm to 1 μ m in thickness.

Claim 32 (New): The vapor deposition material of Claim 26, wherein the entire surface of the polycrystalline body, sintered body, or single crystal is covered with a fluoride layer.

Claim 33 (New): The vapor deposition material of Claim 26, comprising a polycrystalline body covered with a fluoride layer.

Claim 34 (New): The vapor deposition material of Claim 26, comprising a sintered body covered with a fluoride layer.

Claim 35 (New): The vapor deposition material of Claim 26, comprising a single crystal covered with a fluoride layer.

Claim 36 (New) The vapor deposition material of Claim 26, wherein $0.25 \le X < 2$.

Claim 37 (New) The vapor deposition material of Claim 26, wherein $0.5 \le X < 2$.

Claim 38 (New) The vapor deposition material of Claim 26, wherein $1 \le Y \le 4$.

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Claim 39 (New) The vapor deposition material of Claim 26, wherein the fluoride layer is a material selected from the group consisting of $MO_{0.5}F$, $MO_{0.25}F_{1.25}$, MOF_2 , MOF_3 , and $MOF_{0.66}$.

Claim 40 (New) The vapor deposition material of Claim 26, wherein the film body is free of a substrate.